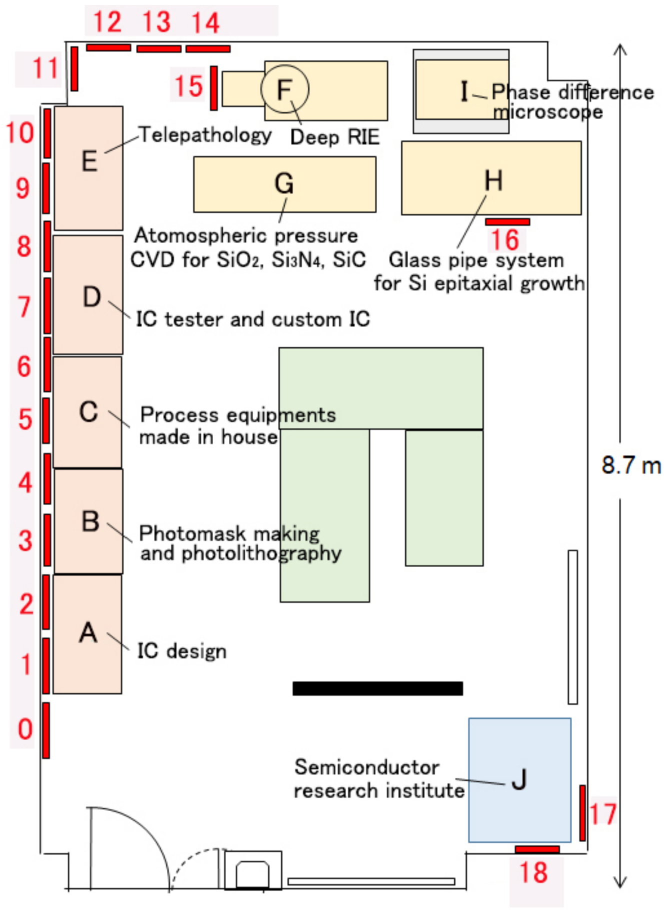
0 In-house IC and equipment room



Poster

0 In-house IC and equipment room
1 Design (1) CAD
2 Design (2) layout
3 Mask making, photolithography
4 Wafer process (1) process sequence, etching
5 Wafer process (2) oxidation, diffusion, CVD
6 Wafer process (3) ion implantation, sputtering
7 IC tester
8 Fabricated custom IC (1) (channel length 10 μm)
9 Telepathology by improved telecommunication
10 Revolution of telemedicine
11 Demonstration of Telepathology by Hi-vision movie
12 Assembly, measurement
13 Fabricated custom IC (2) barrel shifter, integrated capacitive pressure sensor
14 Deep reactive ion etching (Deep RIE) system
15 Effective drawing of process chart
16 Si epitaxial growth and optical observation of defect (Semiconductor research institute)
17 From “Semiconductor Research Institute (SRI)” to “Nishizawa Memorial Research Center”
18 Nishizawa memorial room

In-house IC and equipment room from entrance

Message from Prof.Nishizawa

Semiconductor Research Institute and Nishizawa memorial room

In-house IC design, fabrication and test

Glass pipe gas line for Si epitaxial growth system (right), atmospheric pressure CVD system (poly Si, Si_3N_4, SiO_2) (left)